

CLAIMS

1. A method for cleaning a microstructure comprising fluidizing a cleaning agent composition essentially containing carbon dioxide and a cleaning component under high pressure, and bringing the cleaning agent composition into contact with a microstructure to remove a substance adhering to the microstructure, wherein hydrogen fluoride is used as the cleaning component.

2. The method according to claim 1, wherein the hydrogen fluoride concentration in the cleaning agent composition is 0.0001 to 0.5% by mass.

3. The method according to claim 1, wherein the cleaning agent composition is prepared by mixing hydrofluoric acid and high-pressure carbon dioxide.

4. The method according to claim 3, wherein the water content in the cleaning agent composition is controlled to 0.0001 to 0.5% by mass.

5. The method according to claim 1, wherein the cleaning agent composition further contains 1% by mass or more an alcohol.

6. A microstructure cleaned by the method according to claim 1.